

Atty. Dkt. No. 039153-0441 (G0406)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: Philip A. Fisher et al.  
Title: ENHANCED TRANSISTOR GATE  
USING E-BEAM RADIATION  
Appl. No.: 10/017,855  
Filing Date: 12/14/2001  
Examiner: To be assigned  
Art Unit: To be determined

CERTIFICATE OF MAILING  
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Chris Escavaille

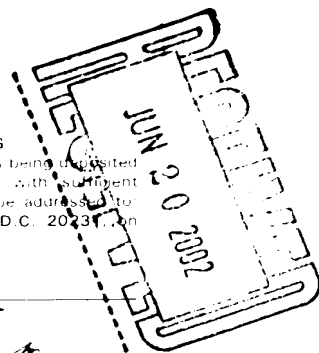
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*Chris Escavaille*

(Signature)

March 25, 2002

(Date of Deposit)



**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. §§ 1.97-98 and in accordance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant submits herewith the references listed on the attached Form PTO-1449 to the Examiner such that they may be considered and made of record in the above-identified application. A copy of each reference is enclosed.

Respectfully submitted,

Date

3-25-02

By

*Joseph N. Ziebert*

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Form PTO-1449  
(MODIFIED)U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.

SERIAL NO.

39153/441 (G0406)

10/017,855

APPLICANT

Philip A. Fisher et al.

## INFORMATION DISCLOSURE CITATION

MAR 29 2002

FILING DATE

GROUP ART UNIT

(Use several sheets if necessary)

FED. 12/14/2001

To be determined

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
	A1	09/819,342		Shields et al.			03/28/01
	A2	09/819,343		Gabriel et al.			03/28/01
	A3	09/819,344		Okoroanyanwu et al.			03/28/01
	A4	09/819,552		Gabriel et al.			03/28/01
	A5	09/819,692		Okoroanyanwu et al.			03/28/01
	A6	09/820,143		Okoroanyanwu et al.			03/28/01
	A7	6,107,172	08/22/00	Yang et al.	438	585	
	A8	6,103,457	08/15/00	Gabriel	430	318	
	A9	5,965,461	10/12/99	Yang et al.	438	717	
	A10	5,003,178	03/26/91	Livesay	250	492.300	

## FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION	
						YES	NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

A11	Livesay, W. R., "Large-area electron-beam source," Journal of Vacuum Science & Technology B, Vol. 11, No. 6, Nov./Dec. 1993, pp. 2304-2308, American Vacuum Society
A12	Yank, J. J. et al., "Electron Beam Processing for Spin-on Polymers and its Applications to Back-End-of-Line (BEOL) Integration," Materials Research Society Symposium Proceedings, Vol. 511, 1998, pp. 49-55, Materials Research Society
A13	Ross et al. "Plasma Etch Characteristics of Electron Beam Processed Photoresist," The Society of Photo-Optical Instrumentation Engineers, Vol. 2438, 1995, pp. 803-816, SPIE- The International Society for Optical Engineering
A14	Grün, Von A.E., "Lumineszenz-photometrische Messungen der Energieabsorption im Strahlungsfeld von Elektronenquellen Eindimensionaler Fall in Luft", Zeitschrift für Naturforschung; Vol. 12a, 1957, pp. 89-95, Publisher: Zeitschrift für Naturforschung; full English Translation attached (11 pgs.)

EXAMINER

DATE CONSIDERED

\* EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.